

**Amendments to the Specification:**

Please replace the paragraph beginning on page 13, line 5, with the following rewritten paragraph:

In addition, a Z movable mirror 57 is provided on the side surface of the Z tilt stage 52 of the substrate stage ~~PST1~~, PST1 (PST2), and a Z interferometer 58 is provided at a position opposing the Z movable mirror 57. A Z interferometer 58 is provided respectively to the exposure station STE and the measuring station STA. The Z interferometer 58 measures the substrate stage PST, specifically the position of the Z tilt stage 52 in the Z axial direction.

Please replace the paragraph beginning on page 30, line 14, with the following rewritten paragraph:

The second substrate stage PST2, for which the measurement process (steps SA1 to SA6) at the measuring station STA as discussed above has ended, moves to the exposure station STE. Furthermore, the control apparatus CONT uses the second liquid collection mechanism 40 to collect the liquid LQ on the substrate P and the substrate stage PST (PST2) before the substrate stage PST (PST2) moves from the measuring station STA to the exposure station STE. Meanwhile, the first substrate stage PST1, which was disposed at the exposure station STE, moves to the measuring station STA. At this point, the exposure process is performed at the exposure station STE on the substrate P that was held by the first substrate stage PST1 in parallel with the measurement process performed on the second substrate stage PST2 at the measuring station STA.

Please replace the paragraph beginning on page 35, line 22, with the following rewritten paragraph:

Then, during the scanning and exposure of each of the shot regions S1 to S24, each of the shot regions S1 to S24 which are on the substrate P, and the mask M are aligned based on the information of the positional relationship between the fiducial mark PFM and each of the shot regions S1 to ~~S20~~S24, and the projection position information of the pattern image of the mask M derived using the fiducial mark MFM.

Please replace the paragraph beginning on page 37, line 3, with the following rewritten paragraph:

Furthermore, the surface information (the Z position information within the XY plane) of the surface of the substrate P may be detected using the focus leveling detection system 70 of the exposure station STE during scanning and exposure, and used to confirm the results of adjusting the positional relationship between the surface of the substrate P and the plane of the image, which formed through the projection optical system PL and the liquid LQ.

Please replace the paragraph beginning on page 37, line 8, with the following rewritten paragraph:

Furthermore, with the embodiments discussed above, the adjustment of the positional relationship between the surface of the substrate P and the plane of the image, which formed through the projection optical system PL and the liquid LQ, is performed by driving the Z tilt stage 52 that holds the substrate P, but the image plane may be aligned with the surface of the substrate P by moving the mask M, some of the plurality of lenses that constitute the projection optical system PL, and the like.

Please add the following new paragraph after the paragraph ending on line 21 of page 56:

As far as is permitted, the disclosure in all of the patent documents such as Japanese patent publication and U.S. patent and the like cited in the above respective embodiments and modified examples, are incorporated herein by reference.